



FORM PTO-1449/A and B (Modified)

**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**

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APPLICANT: Berrian, et al.

GROUP ART UNIT: 2881

EXAMINER: Not yet assigned

Sheet 1 of 1

**U.S. PATENT DOCUMENTS**

Examiner's Initials#	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication or of issue of Cited Document MM-DD-YYYY
		Number	Kind Code		
	1	3,689,766		Freeman	09/05/1972
	2	3,778,626		Robertson	12/11/1973
	3	4,021,675		Shifrin	05/03/1977
	4	4,421,988		Robertson et al.	12/20/1983
	5	4,494,005		Shibata et al.	01/15/1985
	6	4,726,689		Pollock	02/23/1988
	7	4,922,106		Berrian et al.	05/01/1990
	8	4,980,562		Berrian et al.	12/25/1990
	9	5,229,615		Brune et al.	07/20/1993
	10	5,350,926		White et al.	09/27/1994
	11	5,406,088		Brune et al.	04/11/1995
	12	5,898,179		Smick et al.	04/27/1999
	13	5,981,961		Edwards et al.	11/09/1999

**FOREIGN PATENT DOCUMENTS**

Examiner's Initials#	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document (not necessary)	Date of Publication of Cited Document MM-DD-YYYY	Translation (Y/N)
		Office/ Country	Number	Kind Code			
	14	EP	0398269 A2		Nissin Electric Company, Ltd.	11/22/1990	N
	15	EP	0542560 A1		Toshiaki Sugiyama	05/19/1993	N

**OTHER ART - NON PATENT LITERATURE DOCUMENTS**

Examiner's Initials#	Cite No	Include name of the author (in CAPITAL LETTERS) title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, relevant page(s), volume-issue number(s), publisher, city and/or country where published.	Translation (Y/N)
	16	S. RADOVANOVIĆ, R. LIEBERT, P. COREY, J. CUMMINGS, G. ANGEL, J. BUFF, "In Situ Charging Potential Monitoring for a High Current Ribbon Beam", VSEA Technical Publications, Doc. No. 0SEB358, 9/05/2000, pp. 1-4	
	17	J.C. OLSON, A. RENAULT, J. BUFF, "Scanned Beam Uniformity Control in the VHSI 810 Ion Implanter", 1998 International Conference on Ion Implantation Technology Proceedings, Kyoto, Japan, IEEE 1999, pp. 169-172	

EXAMINER

DATE CONSIDERED

#EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

\*a copy of this reference is not provided as it was previously cited by or submitted to the office in a prior application, Serial No. \_\_\_\_\_, filed \_\_\_\_\_, and relied upon for an earlier filing date under 35 U.S.C. § 120 (continuation, continuation-in-part, and divisional applications).

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